

IN THE CLAIMS

Please cancel claims 2, 3 and 16 without prejudice or disclaimer of the subject matter contained therein.

Please amend the claims as follows:

1. (Three Times Amended) A method of preventing generation of particles in a chamber, the method comprising:

mounting a substrate within a chamber of a gas-exposure equipment;

decreasing a pressure within the chamber;

injecting a surface treatment gas into the chamber, the surface treatment gas converting a surface of the substrate into an organic material;

increasing the pressure within the chamber to greater than or equal to atmospheric pressure by injecting a nitrogen gas into the chamber; and

drawing out the surface treatment gas from the chamber while injecting the nitrogen gas into the chamber and preventing atmospheric air and moisture from penetrating the chamber.

7. (Amended) The method as claimed in claim 6, wherein the injecting nitrogen gas into the chamber includes injecting the nitrogen gas through the ejection lines.

13. (Amended) A method to prevent generation of contaminating particles in a chamber, the method comprising:

evacuating an ordinary gas within said chamber;

injecting a treatment gas into said chamber to treat a surface of a substrate;

increasing a pressure in said chamber to greater than or equal to atmospheric pressure by injecting a moisture displacing gas into the chamber; and

withdrawing said treatment gas from said chamber while injecting the moisture displacing gas into said chamber and preventing atmospheric air from entering the chamber.